

Semiconductor Science and Information Devices https://journals.bilpubgroup.com/index.php/ssid

ARTICLE

Analysis of the Effect of Radiation Defects by Low-energy Protons on Electrophysical Properties of Silicon *N***⁺ -***P***-***P***⁺ Structure**

*Bogatov N.M.** *[,](https://orcid.org/0000-0002-9301-4545) Grigoryan L.R., Kovalenko M.S., Volodin V.S.*

Department of Physics and Information Systems, Kuban State University, Krasnodar, 350040, Russia

ABSTRACT

Nowadays, radiation engineering is a promising direction in the creation of semiconductor devices. The proton irradiation is used to controllably change the optical, electrical, recombination, mechanical and structural properties of the semiconductors. Low-energy protons make it possible to purposefully change material properties near the surface where the $n^{\text{+}}$ - p junction is located. In this paper, the impact of low-energy protons on the electro physical parameters of n^+ - p - p^+ silicon photoelectric converters (SPC) is analyzed. The current-voltage characteristics and switching time of these SPCs are measured. The switching time is determined using rectangular bipolar voltage pulses with an amplitude of 10 mV, a frequency of 200 kHz, or a frequency of 1 MHz. A theoretical and experimental analysis of the obtained results is performed. The comparison of experimental data with the results of calculations shows that protons with an energy of 180 keV and a dose of 10^{15} cm⁻² create two regions in the space charge region of the n^+ -p junction with different switching times of 4.2×10^{-7} s and 5.5×10^{-8} s. SPC frequency characteristics have been improved by reducing the effective lifetime by 5-10 times. This effect can be used to create high-speed photodiodes with an operating modulation frequency of 18 MHz.

Keywords: Silicon; *n*⁺ -*p* junction; Lifetime; Proton; Pulse characteristic

1. Introduction

radiation on the properties of semiconductor materials and devices is increasing due to the increasing use of these processes in industrial technologies un-

The relevance of studies of the effects of ionizing

*CORRESPONDING AUTHOR:

Bogatov N.M., Department of Physics and Information Systems, Kuban State University, Krasnodar, 350040, Russia; Email: [bogatov@phys.kub](mailto: bogatov@phys.kubsu.ru)[su.ru](mailto: bogatov@phys.kubsu.ru)

ARTICLE INFO

Received: 8 September 2023 | Revised: 1 November 2023 | Accepted: 3 November 2023 | Published Online: 10 November 2023 DOI: <https://doi.org/10.30564/ssid.v5i1.6014>

CITATION

Bogatov, N.M., Grigoryan, L.R., Kovalenko, M.S., et al., 2023. Analysis of the Effect of Radiation Defects by Low-energy Protons on Electrophysical Properties of Silicon *N⁺ -P-P⁺* Structure. Semiconductor Science and Information Devices. 5(1): 18-25. DOI: [https://doi.org/10.30564/](https://doi.org/10.30564/ssid.v5i1.6014) [ssid.v5i1.6014](https://doi.org/10.30564/ssid.v5i1.6014)

COPYRIGHT

Copyright © 2023 by the author(s). Published by Bilingual Publishing Group. This is an open access article under the Creative Commons Attribution-NonCommercial 4.0 International (CC BY-NC 4.0) License. [\(https://creativecommons.org/licenses/by-nc/4.0/\)](https://creativecommons.org/licenses/by-nc/4.0/).

der controlled exposure, as well as the use of devices under uncontrolled environmental exposure $[1-6]$.

The electrophysical characteristics of semiconductor structures with an n^{\dagger} -*p* junction depend on the volume and surface recombination rates, the impurities and radiation defects distributions. The parameters of volume and surface recombination were measured by the photoconductivity decay method $[7,8]$. Methods for determining recombination parameters are being improved. Pulsed illumination was used to determine the effect of structural defects on recombination parameters in the bulk of polycrystalline silicon and the p-n junction [9]. Measuring recombination parameters using the photoconductivity method, which is recorded using microwave radiation, allows you to monitor the results of technological processes [10].

The transient characteristics of semiconductor devices can be improved by irradiating them with protons [11]. The influence of irradiation with low-energy protons and the temperature of irradiated samples on the parameters of current-voltage characteristics (CVC) of silicon photoelectric converters (SPC) and the distribution of radiation defects is shown in articles $[12,13]$. As a result of irradiation with low energy protons, the switching time of SPC decreases $[14]$. The authors of the article $[15]$ draw attention to the relevance of numerical modeling of the effects of irradiation with light and ionizing particles in semiconductor devices.

From a scientific and practical point of view, it is necessary to study the change in the electrical properties of SPCs under the influence of low-energy protons and evaluate the possibility of reducing their switching time in a dynamic mode.

2. Research methods

Photoelectric converters are a wide class of devices that convert the energy of electromagnetic radiation into electrical energy $[16-18]$. These devices include the semiconductor photoelectric converter that performs the functions of a primary converter. The frequency characteristics of photovoltaic converters depend on the switching time of the semiconductor photoelectric converters.

The subject of the study is the properties of n^+ p - p ⁺ SPCs. The samples' parameters: concentration of equilibrium holes in the base— $p_0 \approx 10^{15}$ cm⁻³, thickness of diffusion n^{\dagger} -*p* and *p*-*p*⁺ layers—*d_n* ≈ *d_p* ≈ 0.45 μ m, base thickness— $L \approx 200 \mu$ m, area— $S \gg 1$ cm², phosphorus concentration on the surface of n^+ layer— $N_P \approx 10^{20}$ cm⁻³, boron concentration on the surface of p^+ layer— $N_B \approx 10^{20}$ cm⁻³.

Proton irradiation was performed from the *n*⁺ layer side. Radiation dose $F_p = 10^{15}$ cm⁻². Sample irradiation conditions (proton energy E_n , sample temperature *Tp*): N1 – $E_p = 180$ keV, *Tp* = 83 K; N2 – $E_p = 40 \text{ keV}, Tp = 83 \text{ K}; \text{N}3 - E_p = 40 \text{ keV}, T_p = 300$ K. The control group of 7 samples with very similar electrophysical characteristics N4 was not irradiated.

The dark CVC of the SPC was measured using an **IPP1** device at a temperature $T = 300 \text{ K}$ ^[12,13] (**Figure 1**).

Figure 1. CVC of the studied SPC.

Note: 1—N1, 2—N2, 3—N3, 4—N4.

Transient characteristics were measured in the dark using a DSOX2022A digital oscilloscope, including the functions of a voltage pulse generator and a multimeter $[14]$, using bipolar rectangular voltage pulses with a constant amplitude $Um = 10$ mV and a frequency $f = 200$ kHz and $f = 1$ MHz. The measured dependences of voltage *U* on time *t* are shown in **Figures 2 and 3**.

Figure 2. Transient characteristics of the SPC at a frequency 200 kHz.

Note: 1**—**N1, 2**—**N2, 3**—**N3, 4**—**N4.

Figure 3. Transient characteristics of the SPC at a frequency 1 MHz.

Note: 1**—**N1, 2**—**N2, 3**—**N3, 4**—**N4.

3. Analysis of the research results

The depth distributions of the average number of interstitial silicon G_{S_i} , vacancies G_V , and divacancies G_W created by one proton per unit of the projective path length were calculated using the model of the formation of primary radiation defects (PRD)^[19] (**Figure 4**). The rate of formation of radiation defects depends on the concentration of impurities and the temperature of the samples $[12,13,19,20]$.

Protons with $E_p = 40$ keV create PRDs in the n^+ layer at a depth of 0.41 μm. In this case, the number of PRDs at $T_p = 300$ K is several times greater than at $T_p = 83$ K, as well as the number of PRDs created by protons with $E_p = 180$ keV at $T_p = 83$ K (**Figure 4**). Protons with $E_p = 40 \text{ keV}$ change the properties of the n^+ layer, so the CVC of the irradiated samples N2, N3 and the unirradiated sample N4 are different (**Figure 1**). However, the transient characteristics of these samples differ little. Consequently, they do not depend on the electrical properties of the n^+ layer.

Figure 4. The distributions of PRD created by a proton with energy E_p at the temperature T_p of the irradiated SPC.

Protons with $E_p = 180$ keV create PRDs in the SCR of the n^{\dagger} -*p* junction up to 1.51 μ m (**Figure 4**). PRDs are absent in the base of SPC under these irradiation conditions. The transient characteristics of SPC N1 differ from the transient characteristics of SPC N2, N3, N4 (**Figures 2 and 3**), therefore the transient characteristics of the SPCs are determined by the parameters of the radiation-damaged SCR of the n^{\dagger} -*p* junction. The CVC of SPC N1 differs from the CVC of SPC N2, N3, N4 (**Figure** 1), which is results explained by a change in the electrophysical characteristics of the SCR of SPC N1 under proton irradiation. CVC of SPC N2, N3, N4 (**Figure 1**), which is explained by a change in the

nd divacancies Shockley^[21] proposed the fundamental system of projective differential equations (FSDE) for the analysis of the $\frac{1}{2}$ model of the transport of charge carriers in semiconductors with n^{\dagger} -*p* junction.

$$
\begin{cases}\n\vec{j}_n = \mu_n n \vec{v}_0 - D_n \vec{v}_n \\
0 \\
\vec{j}_p = -\mu_p p \vec{v}_0 - D_p \vec{v}_p \\
0 \\
\frac{\partial n}{\partial t} + (\vec{v}; \vec{j}_n) = G - R \\
0 \\
\frac{\partial p}{\partial t} + (\vec{v}; \vec{j}_p) = G - R \\
0 \\
\Delta \varphi = -\frac{q}{\varepsilon \varepsilon_0} (p - n + N_D^+ - N_A^-) \\
0\n\end{cases}
$$
\n(1)

different The system of equations, (1) contains unknown numerations of variables: *n*—the concentrations of electrons, *p*—the

concentrations of holes, \overrightarrow{j}_n —the density of the electron flow, \overline{j}_p —the density of the hole flow, φ —the Radi potential of the internal electric field; specified sili-
gy 40 k $\frac{d}{dt}$ = $\frac{d$ coefficient of the state of the rate of the rate of the rate of the rate of the electron-hole pairs, and t the rate of volume generation of the electron-hole increase pairs, R—the rate of volume recombination of the electron-hole pairs, N_D^+ —concentration of the ioncon parameters: μ_n —mobility of the electrons, D_n — that the diffusion coefficient of the electron, μ_p —mobility of length a the holes, D_p —diffusion coefficient of the hole, G — a res concentrations of electrons, *p*—the concentrations of holes, jሬሬԦ ized donors, N_A —concentration of the ionized ac*ceptors, q—elementary charge, ε—permittivity, ε*₀— \vec{r} flow \vec{i} the density of the hole flow \vec{r} the con parameters: μ_n —mobility of the electrons, D_n electric field; specified silvers: μ_p moothly of the electrons, μ_p dielectric constant.

The system of equations, (1) contains unknown variables: *n* — the

The system of equations, (1) contains unknown variables: *n* — the

*εε*⁰

[∆] ^φ ൌെ *^q*

From the system of equations, (1) follows the dependence of the electric current *I* on the voltage U_{np} at the *n*-*p* junction of the following form $^{[22]}$.

$$
I = I_0 \left[\exp\left(\frac{qU_{np}}{kT}\right) - 1 \right] + I_r \left[\exp\left(\frac{qU_{np}}{akT}\right) - 1 \right] + \frac{U_{np_s}}{R_{sh}} \tag{2}
$$

$$
U_{np} = U - IR_s \tag{3}
$$

neutral n^+ layer and base; I_r —recombination current recombination current due to SCR; *a*—the coefficient of nonideality of the *n*-*p* junction; *Rsh*—shunting resistance of the *n*-*p* junction; *U*—electrical voltage at the concentrated sequential resistance; *k*—Boltzmann constant. It is necessary to determine which region σ ² of the SPC gives the main contribution to the ex- P perimental dependences CVC. For this purpose, the approximated by a theoretical dependence (4) . due to SCR; *a*—the coefficient of nonideality of the $n-p$ junction; R_{sh} —shunting resistance of the *n*-*p* junction; *U*—electrical voltage at the contacts; R_s where I_0 —reverse saturation current due to quasiexperimental dependencies *I*(*U*) (**Figure 1**) must be

$$
I = I_0 \left(\exp\left\{ \frac{e(U - IR_s)}{akT} \right\} - 1 \right) + \frac{U - IR_s}{R_{sh}} \tag{4}
$$

in the parameters of $\sigma \sigma$ calculated as a result of **a** iii the approximation are given in the table. The nonideality coefficient of the *n-p* junction $a = 1.6$ for the . $\frac{1}{2}$ voltage $U < 0.6$ V ^[22]. The parameters of CVC calculated as a result of non-irradiated sample N4 (table). It means that the $\delta n(x, t) = \sum [A_{\alpha}(x) - B_{\alpha}(x) \cdot \exp(-\frac{t-t_0}{2}) - 1]$ (7) SCR gives the main contribution to the CVC at the $\sum_{i=1}^{\infty} \binom{n}{i}$ and $\sum_{i=1}^{\infty} \binom{n}{i}$ $\frac{1}{\sqrt{2}}$ structure of the SCR and $\frac{1}{\sqrt{2}}$

180 keV disrupt the structure of the SCR and reduce $\delta p(x, t) = \sum_i \left[A_{pi}(x, t) \right]$ the lifetime of the electrons and holes. Therefore, the w contribution of the SCR to the CVC and the nonide-
B that *a* = 2.6 for sample N1 (table). ality coefficient increase, so that $a = 2.6$ for sample

elec- N1 (table).

 — a result, the contribution of the *n*-region to the CVC Radiation defects created by protons with energy 40 keV change the properties of the *n*-region so that the concentration of the electrons, the diffusion length and the lifetime of the holes are reduced. As increases. The quasineutral region contributes to the CVC with a non-ideality coefficient $a = 1$ ^[22]. Therefore, for samples N2 and N3 the coefficient of nonideality *a* is close to 1 (table).

The value of I_{0r} in sample N2 is an order of magnitude less than in sample N3 (table), because G_{S_i} , G_V , created in the *n*-region at $T_p = 83$ K, are smaller than at $T_p = 300$ K (**Figure 4**).

 $-\frac{U_{np_s}}{R}$ (2) decrease in the resistance of surface. The decrease of e voltage U_{np} and at I_p 500 H (Figure 1).
The irradiated SPCs have less value of R_s than $\frac{1}{2}$ are determined by the parameters of the $\frac{1}{2}$ are determined by the parameters of R_{sh} (2) R_{sh} in irradiated SPCs may be caused by an increase (3) in the number of surface states at the ends of the $n-p$ junction. \mathcal{L} in proposed the functions of differential equations of \mathcal{L} \mathcal{L} proposed the fundamental system of differential equations of differential equations of differential equations of \mathcal{L}

lue to quasi-
When measuring the pulse characteristics, the condition of the small amplitude of the voltage at the contacts was fulfilled (5).

$$
qU_m/kT < 1\tag{5}
$$

linequality (5) means that a mode of low injection of nonequilibrium electrons and holes in the *n*⁺ and *p* regions is realized. According to the experimental conditions, there is no light generation of electrons and holes $G = 0$. Then the FSDE (1) is simplified so that the solution for the concentration of electrons and holes has the form (6) . \overline{a} $G = 0$. Then the F₂ for the concentration of electrons $\overline{\mathfrak{g}}$

$$
n = n_0 + \delta n, p = p_0 + \delta p \tag{6}
$$

where n_0 and p_0 are the solution of the system (1) and $\vec{J}_n = 0$, $\vec{J}_p = 0$. To determine δ*n*, δ*p* we use substitution. electric field; specified silicon parameters: μn —mobility of the electrons, *Dn*—

$$
\delta n(x, t) = \sum_{i} \left[A_{ni}(x) - B_{ni}(x) \cdot \exp\left(-\frac{t - t_0}{\tau_i}\right) - 1 \right] \quad (7)
$$

Radiation defects created by protons with energy

\n
$$
\delta p(x, t) = \sum_{i} \left[A_{pi}(x) - B_{pi}(x) \cdot \exp\left(-\frac{t - t_0}{\tau_i}\right) - 1 \right] \tag{8}
$$
\n180 keV disrupt the structure of the SCR and reduce

f α = α *t*₀ $\leq t \leq t_m$, $t_m - t_0 = (2f)^{-1}$. The functions A_{ni}(X)*,* α he nonide- $B_{ni}(X)$, $A_{pi}(X)$, $B_{pi}(X)$ are the solution of FSDE in are $\frac{1}{2}$ $\frac{1}{2$ for sample quasi-neutral p , n^+ regions and SCR.

The range of switching time values $\tau_j \in (2\Delta t,$ $(4f)^{-1}$) is determined by the duration of the bipolar voltage pulses $(2f)^{-1}$ and the signal sampling step Δt . The SPC SCR makes the main contribution to the ¹ voltage drop $U^{[22]}$. Thus, electrical voltage relaxation processes occur in the SPC with an effective lifetime τ_j depending on the processes in the SCR. v_0 v_0 v_1 v_2 v_3 v_4 v_5 v_6 v_7 v_8 v_9 v_1 v_2 v_3 v_4 v_5 v_6 v_7 v_8 v_9 v_1 v_2 v_3 v_4 v_5 v_6 v_7 v_8 v_9 v_1 v_2 v_3 v_4 v_5 v_6 v_7 v_8

$$
U(t) = \sum_{j} \left[D_j \cdot \exp\left(-\frac{t - t_0}{\tau_j}\right) - C_j \right], \text{ when } t_0 < t < t_m. \tag{9}
$$

of the pulse characteristics (**Figures 2 and 3**) gives close values of the effective lifetime in the SCR for the samples N2, N3, N4 (**Table 1**). Two values $\tau_1 = 4.2 \times 10^7$ When using the dependence (9), the approximation 10^{-7} s, $\tau_2 = 5.5 \times 10^{-8}$ s were found for sample N1.

10⁸ s were found for sample N1. Consequently, the structure of SPC was changed by protons with an energy of 180 keV so, there are two regions in SCR with different values $τ_1$ and $τ_2$. The lifetime τ_2 belongs to the region with a high concentration of the PRD near the Bragg peak at $x = 1.48$ mm (**Figure 4**).

The transient response simulation results are shown in **Figures 5-7**. A decrease of lifetime τ at a given pulse frequency $f = 10$ MHz causes a change in the shape of the transient response. Transient characteristics have a triangular shape with a smaller amplitude and equal length front and rear wave fronts (**Figure 5**) at the values of the parameters $\tau = 2.5 \times$ 10^{-7} s and $\tau = 5 \times 10^{-7}$ s.

A decrease of the τ value at the frequency $f = 10$ MHz reestablishes the shape of the transient characteristics: A reduction of 10 times gives the transient characteristics shown in **Figure 6**, and 50 times the transient characteristics shown in **Figure 7**.

Figure 5. The transient characteristics at pulse frequency $f = 10$ MHz. The lifetime in SCR is $I - \tau = 2.5 \times 10^7$ s, $2 - \tau = 5 \times 10^7$ s.

Figure 6. The transient characteristics at pulse frequency $f = 10$ MHz. The lifetime in SCR is $I - t = 0.25 \times 10^7$ s, $2 - t = 0.5 \times 10^7$ s.

Figure 7. The transient characteristics at pulse frequency $f = 10$ MHz. The lifetime in SCR is $I - \tau = 0.05 \times 10^{-7}$ s, $2 - \tau = 0.1 \times 10^{-7}$ s.

4. Conclusions

Proton irradiation makes it possible to locally create the electrically and recombinationally active defects in semiconductors with a maximum concentration in the Bragg peak region. Radiation defects created by protons with an energy 180 keV and a dose 10^{15} cm⁻² disrupt the structure of the SCR of the n^{\dagger} -*p* junction of silicon devices and reduce the lifetime of charge carriers, which leads to a significant increase in the contribution of SCR to the dark electric current in stationary mode. It was found that two regions with different values of effective lifetimes $\tau_1 = 4.2 \times 10^{-7}$ s, $\tau_2 = 5.5 \times 10^{-8}$ s were formed in the SCR under the exposure of the proton irradiation. The value of τ_2 is an order of magnitude less than in non-irradiated devices.

Based on the results of the simulation of transient characteristics, it can be concluded that in order to improve the frequency characteristics at a frequency 10 MHz the effective lifetime should be reduced by $5 \div 10$ times. However, in this case, an increase in the dose by 10 times will not lead to an inversely proportional decrease in the effective lifetime. The reason is that the concentration of formed PRDs in the Bragg peak region is much higher than the concentration of the main impurities in silicon grown by the Czochralski method (phosphorus, boron, oxygen, carbon) and other defects interacting with PRD at the stage of formation of secondary radiation defects (SRD). Therefore, direct or indirect annihilation of interstitial silicon and vacancies limits the concentration of recombination active SRDs. Consequently, the task of improving of the frequency characteristics of semiconductor devices cannot be solved only by increasing the radiation dose, but must be solved in combination with the formation of the semiconductor structure and impurity composition.

Author Contributions

Bogatov N. M.—problem statement, research management, article writing.

Grigoryan L. R.—transient response measurement.

Kovalenko M. S.—modeling and calculations. Volodin V. S.—CVC measurement.

Conflict of Interest

The authors declare no conflict of interest.

Acknowledgement

We thank Yu.A. Agafonov and V.I. Zinenko (Institute of Microelectronics Technology and High Purity Materials of the Russian Academy of Sciences) for irradiation of the samples.

References

[1] Abdullaeva, I.A., Abdinova, G.D., Tagiyev, M.M., et al., 2021. Effect of gamma irradiation on the electrical properties of extruded Bi_{85}S b₁₅<Te> samples. Inorganic Materials. 57, 887-892.

- [2] Li, J., Aierken, A., Liu, Y., et al., 2021. A brief review of high efficiency III-V solar cells for space application. Frontiers in Physics. 8, 631925.
- [3] Siddiqui, A., Usman, M., 2021. Proton irradiation in simplified PERC silicon solar cells: A simulation-based framework. ECS Journal of Solid State Science and Technology. 10(5), 055007.
- [4] Weiss, C., Park, S., Lefèvre, J., et al., 2020. Electron and proton irradiation effect on the minority carrier lifetime in SiC passivated p-doped Ge wafers for space photovoltaics. Solar Energy Materials and Solar Cells. 209, 110430.
- [5] Serge, T.G., Bernard, Z., Bruno, K., et al., 2019. Theoretical study of proton radiation influence on the performance of a polycrystalline silicon solar cell. International Journal of Photoenergy. 1-7.
- [6] Gubarev, V.N., Semenov, A.Y., Surma, A.M., et al., 2011. Applying proton irradiation for performance improvement of power semiconductors. Power Electronics Europe. 3, 35-38.
- [7] Anfimov, I.M., Kobeleva, S.P., Pylnev, A.V., et al., 2017. On the problem of determining the bulk lifetime by photoconductivity decay on the unpassivated samples of monocrystalline silicon. Russian Microelectronics. 46, 585-590.
- [8] Koshelev, O.G., Vasiljev, N.G., 2017. Separate determination of the photoelectric parameters of n^+ -p (n)-p⁺ silicon structure base region by noncontact method based on measurements of quantum efficiency relationships at two wavelengths. Modern Electronic Materials. 3(3), 127-130.
- [9] Sam, R., Zouma, B., Zougmoré, F., et al., 2012. 3D determination of the minority carrier lifetime and the pn junction recombination velocity of a polycrystalline silicon solar cell. IOP Confer-

ence Series: Materials Science and Engineering. 29(1), 012018.

- [10] Bscheid, C., Engst, C.R., Eisele, I., et al., 2019. Minority carrier lifetime measurements for contactless oxidation process characterization and furnace profiling. Materials. 12(1), 190.
- [11] Kozlov, V.A., Kozlovski, V.V., 2001. Doping of semiconductors using radiation defects produced by irradiation with protons and alpha particles. Semiconductors. 35, 735-761.
- [12]Agafonov, Y.A., Bogatov, N.M., Grigorian, L.R., et al., 2018. Effect of radiation-induced defects produced by low-energy protons in a heavily doped layer on the characteristics of n^+ -p-p⁺ Si structures. Journal of Surface Investigation: X-ray, Synchrotron and Neutron Techniques. 12, 499-503.
- [13]Bogatov, N.M., Grigorian, L.R., Kovalenko, A.I., et al., 2020. Influence of radiation defects induced by low-energy protons at a temperature of 83 K on the characteristics of silicon photoelectric structures. Semiconductors. 54, 196-200.
- [14]Bogatov, N.M., Grigor'yan, L.R., Kovalenko, A.I., et al., 2021. Pulse response characteristics of silicon photovoltaic converters irradiated with low-energy protons. Technical Physics Letters. 47(4), 326-328.
- [15]Hu, Z., Hernández, D.M., Martinez, S.N., 2022. Analysis of radiation effects of semiconductor devices based on numerical simulation Fermi-Dirac. Nonlinear Engineering. 11(1), 252- 259.
- [16] Wen, Y., Zhou, J., 2019. Metamaterial route to direct photoelectric conversion. Materials Today. 23, 37-44.
- [17]Vasilevich, U.P., Nguyen, V.Z., Dziatlau, Y.K., 2018. Photoelectric converter for monitoring lighting systems. Doklady BGUIR. (7), 144- 148.
- [18]Zhu, M., Liu, X., Wang, Y., et al., 2022. Re-

search and design of photoelectric converter for quantum gravimeter. Journal of Physics: Conference Series. 2383(1), 012032.

- [19]Bogatov, N., Grigoryan, L., Klenevsky, A., et al., 2020. Modelling of disordering regions in proton-irradiated silicon. Journal of Physics: Conference Series. 1553(1), 012015.
- [20]Harutyunyan, V., Sahakyan, A., Manukyan, A., et al., 2023. Introduction rates of electrically ac-

tive radiation defects in proton irradiated n-type and p-type Si monocrystals. Journal of Electronic Materials. 1-8.

- [21] Shockley, W., 1949. The theory of p-n junctions in semiconductors and p-n junction transistors. Bell System Technical Journal. 28(3), 435-489.
- [22]Fahrenbruch, A., Bube, R., 2012. Fundamentals of solar cells: Photovoltaic solar energy conversion. Elsevier: Amsterdam.